What is claimed is:

- polycrystalline MgO deposition material for passivation layer of a plasma display panel, comprising:
- a sintered pellet of a polycrystalline MgO, of which MgO purity is more than 99.9% and relative density is more than 90%, wherein a Si concentration in the polycrystalline MgO deposition material is more than 30 ppm and less than 500 ppm.
- 2. The polycrystalline MgO deposition material of claim 1, 10 wherein the Si concentration polycrystalline in the deposition material is in a range of 220 ppm to 480 ppm.
- The polycrystalline MgO deposition material of claim 1, wherein the Si concentration in the polycrystalline 15 deposition material is in a range of 250 ppm to 450 ppm.
 - 4. The polycrystalline MgO deposition material of claim 1, wherein the Si concentration in the polycrystalline MqO deposition material is in a range of 280 ppm to 350 ppm.

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